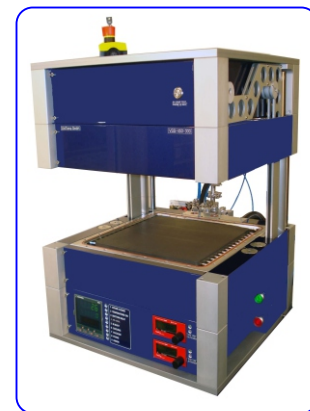


RAPID THERMAL ANNEALING OVENS

for several different applications like annealing for silicon and compound semiconductor wafers (RTA), rapid thermal oxidation (RTO), rapid thermal nitridation (RTN), rapid thermal diffusion from spin-on dopant, crystallization, contact alloying and more.



Model	RTP-100	RTP-100-HV	RTP-150	RTP-150-HV	VPO-1000-300
max. substrate size	100 x100mm	100 x100mm	156 x 156mm	156 x 156mm	300 x 300mm
T _{max}	1200 °C	1200 °C	1000 °C	1000 °C	1000 °C
T °C continuous at	1200 °C	1200 °C	1000 °C	1000 °C	800 °C
Ramp up rate	150 K/sec	150 K/sec	75 K/sec	75 K/sec	40 K/sec
Vacuum up to	10 ⁻³ hPa	10 ⁻⁶ hPa	10 ⁻³ hPa	10 ⁻⁶ hPa	10 ⁻³ hPa
Flowmeter	MFC	MFC	MFC	MFC	FM-EL
Controller	Simatic	Simatic	Simatic	Simatic	Eurotherm
Touch Panel	7"	7"	7"	7"	USB to PC